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(AIUB)  
Faculty of Engineering  
Department of Electrical and Electronic Engineering

**EXPERIMENT NO: 01**

**MID TERM**

**SEC: EE GROUP :07**

**Electronic Device Lab**

**EXPERIMENT TITLE:** *Determination of Characteristic Curve of a Diode.*

**Submitted to:**

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## Table of Contents

Topic	Page No.
TITTLE	03
ABSTRACT / INTRODUCTION	03
THEORY & METHODOLOGY CIRCUIT DIAGRAM	03-05
APPARATUS with Figures	05-07
DATA TABLE	07
CALCULATION	08
SIMULATION	09-11
DISCUSSION	12
REFERENCES	12

## **Title: Determination of Characteristic Curve of a Diode**

### **Abstract:**

A diode is one of the simplest electronic devices. It is a unidirectional device. A diode does not behave linearly with respect to applied voltage and has an exponential I-V relationship. There are two operating regions for the diode, reverse biased region, and forward biased region. The diode is simply a semiconductor pn junction. In addition to being applied as a diode, the pn junction is the basic element of bipolar-junction transistors (BJTs) and field-effect transistors (FETs).

### **Introduction:**

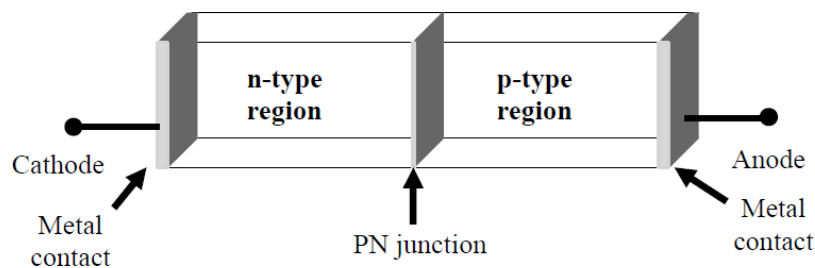
The objectives of the Experiment 1 of the Electronic Devices Lab are,

- i) To become familiar with semiconductor diode.
- ii) To determine the characteristic curve of a semiconductor diode.

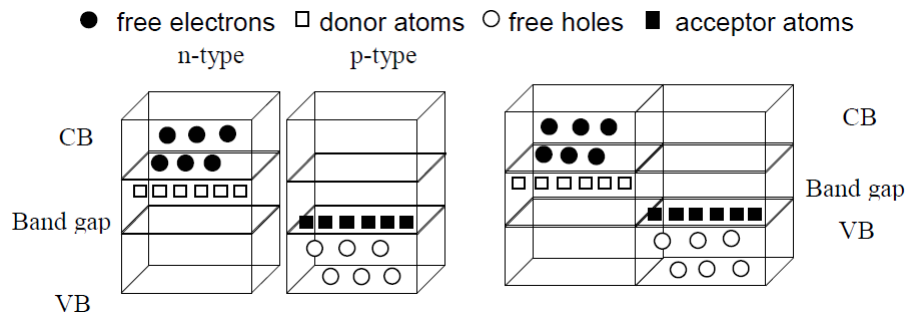
### **Theory & Methodology:**

#### **Diode Structure**

The semiconductor diode is created by simply joining an n-type and a p-type material together [1]. It is a pn junction as shown in Figure 1. As indicated, the pn junction consists of p-type semiconductor material in contact with n-type semiconductor material. A variety of semiconductor materials can be used to form pn junctions like silicon, germanium, gallium arsenide etc. However, we will concentrate on silicon, as this is the most widely used material in microelectronics. In actual practice, both the p and n regions are part of the same silicon crystal. The pn junction is formed by creating regions of different doping (p and n regions) within a single piece of silicon. The material is doped by bringing in additional atoms (impurities). The impurities can be either donors or acceptors atoms. The words acceptor and donor can be associated with donating and accepting electrons.



**Figure 1: pn junction diode structure**



**Figure 2: a) separate pieces b) pn junction**

### **PN Junction**

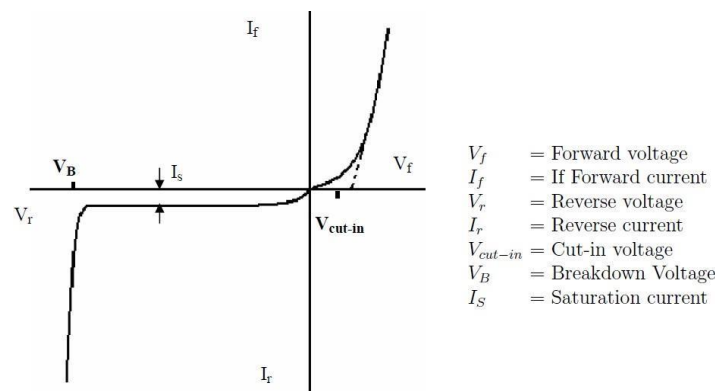
To understand how a pn junction is formed we will start by imagining two separate pieces of semiconductor, one n-type and the other p-type as shown in Figure 2(a). Now we bring the two pieces together to make one piece of semiconductor. This results in the formation of a pn junction (Figure 2(b)).

### **Forward/Reverse Bias Characteristics**

If a negative voltage is applied to the pn junction, the diode is in reverse biased. In response, free holes and electrons are pulled towards the end of the crystal and away from the junction. The result is that all available carriers are attracted away from the junction, and the depletion region is extended. There is no current flow through under such conditions. If the applied voltage is positive, the diode operates in forward bias. This has the effect of shrinking the depletion region. Now, electrons in the p-type end are attracted to the positive applied voltage, while holes in the n-type end are attracted to the negative applied voltage.

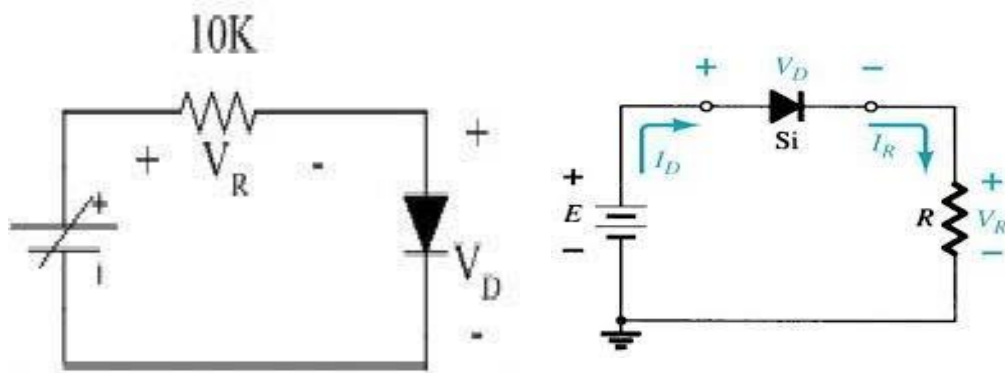
### **Diode Characteristics**

In forward bias condition, a cut-in voltage has to be overcome for the diode to start conduction. In silicon, this voltage is about 0.7 volts. In reverse-bias condition, the current is limited to  $I_S$  (reverse saturation current). For higher value of reverse voltages, the junction breaks down. Figure 3 shows the diode I-V characteristics.



**Figure 3: Diode IV Characteristics**

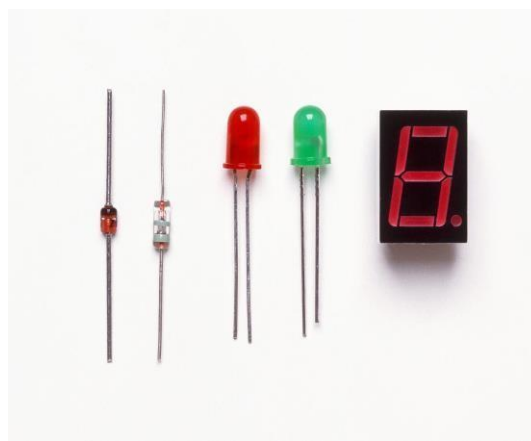
**Circuit Diagram:**



**Figure 4: Circuit diagram for determining diode characteristic**

**Apparatus:**

No.	Apparatus	Quantity
1	Diode	1
2	10 k Resistance	1
3	Project Board	1
4	DC Power Supply	1
5	Multimeter	1



**Fig: Diode**

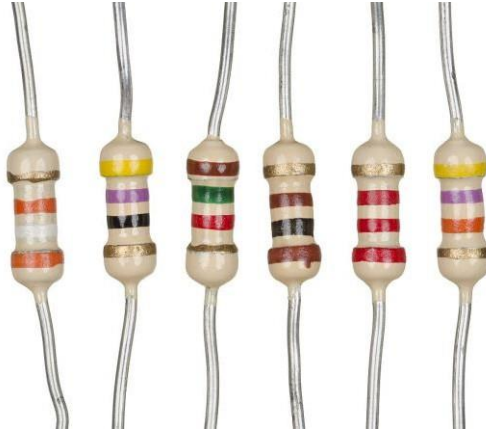


Fig: Resistor

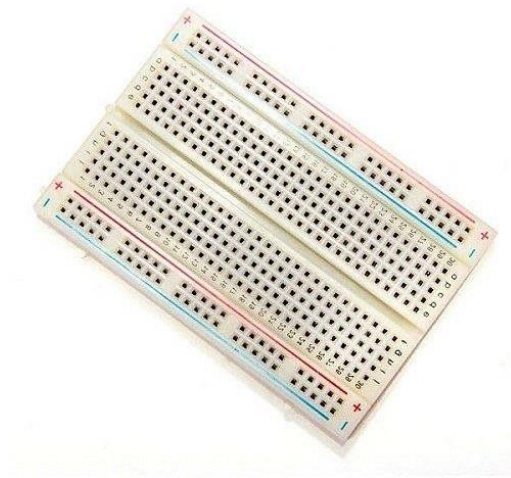


Fig: Project Board



Fig: DC Power Supply



Fig: Multimeter

**Data Table:**

$V_{in}(V)$	$V_d(V)$	$V_r(V)$	$I_d = V_r/(10K)(mA)$
0	0	0	0
0.1	0.056	0.043	0.004
0.3	0.137	0.163	0.016
0.5	0.190	0.309	0.031
0.6	0.210	0.389	0.039
0.7	0.228	0.471	0.047
0.9	0.243	0.556	0.056
2	0.350	1.650	0.165
3	0.396	2.604	0.260
4	0.429	3.571	0.357
5	0.453	4.547	0.455

So, from the theory analysis, we basically know that the voltage remains constant after threshold voltage and the current keeps increasing after that. The same thing we got from our practical analysis. From the data table we seen that, as we kept increasing the input voltage, the forward voltage kept increasing too but the forward current almost stayed in constant state until it reached the threshold voltage. Here it can be seen that the forward voltage kept increasing until it reached the threshold voltage which is 0.7 here for Silicon. And after that current gets to flow while the forward voltage stays in constant state. So, we can easily said that, what we learned in theory, is justified through this practical analysis.

### **Calculations:**

Here,  $I_d = V_R/R$  For

$$V_R = 0$$

$$I_d = 0/10K \text{ Ohm} = 0mA$$

$$\text{For } V_R = 0.043$$

$$I_d = 0.043/10K \text{ Ohm} = 0.0043mA$$

$$\text{For } V_R = 0.163$$

$$I_d = 0.163/10K \text{ Ohm} = 0.0163mA$$

$$\text{For } V_R = 0.309$$

$$I_d = 0.309/10K \text{ Ohm} = 0.0309mA$$

$$\text{For } V_R = 0.389$$

$$I_d = 0.389/10K \text{ Ohm} = 0.0389mA$$

$$\text{For } V_R = 0.471$$

$$I_d = 0.471/10K \text{ Ohm} = 0.0471mA$$

$$\text{For } V_R = 0.556$$

$$I_d = 0.556/10K \text{ Ohm} = 0.0556mA$$

$$\text{For } V_R = 1.650$$

$$I_d = 1.650/10K \text{ Ohm} = 0.165mA$$

$$\text{For } V_R = 2.604$$

$$I_d = 2.604/10K \text{ Ohm} = 0.2604Ma$$

$$\text{For } V_R = 3.571$$

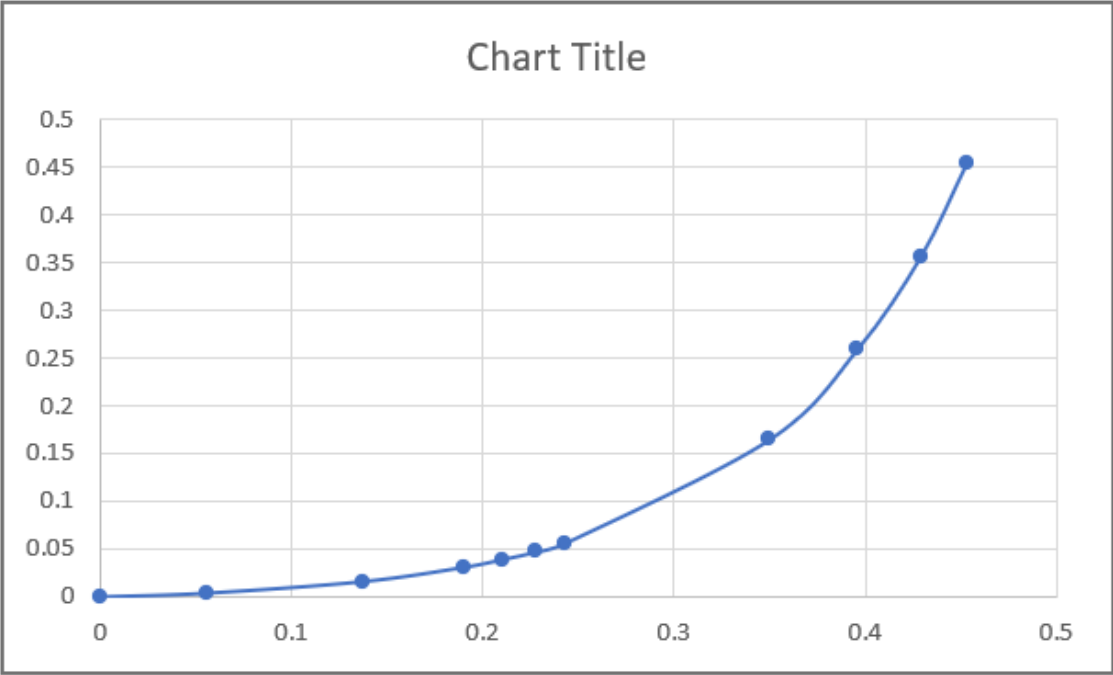
$$I_d = 3.571/10K \text{ Ohm} = 0.3571Ma$$

$$\text{For } V_R = 4.547$$

$$I_d = 4.547/10K \text{ Ohm} = 0.4547mA$$

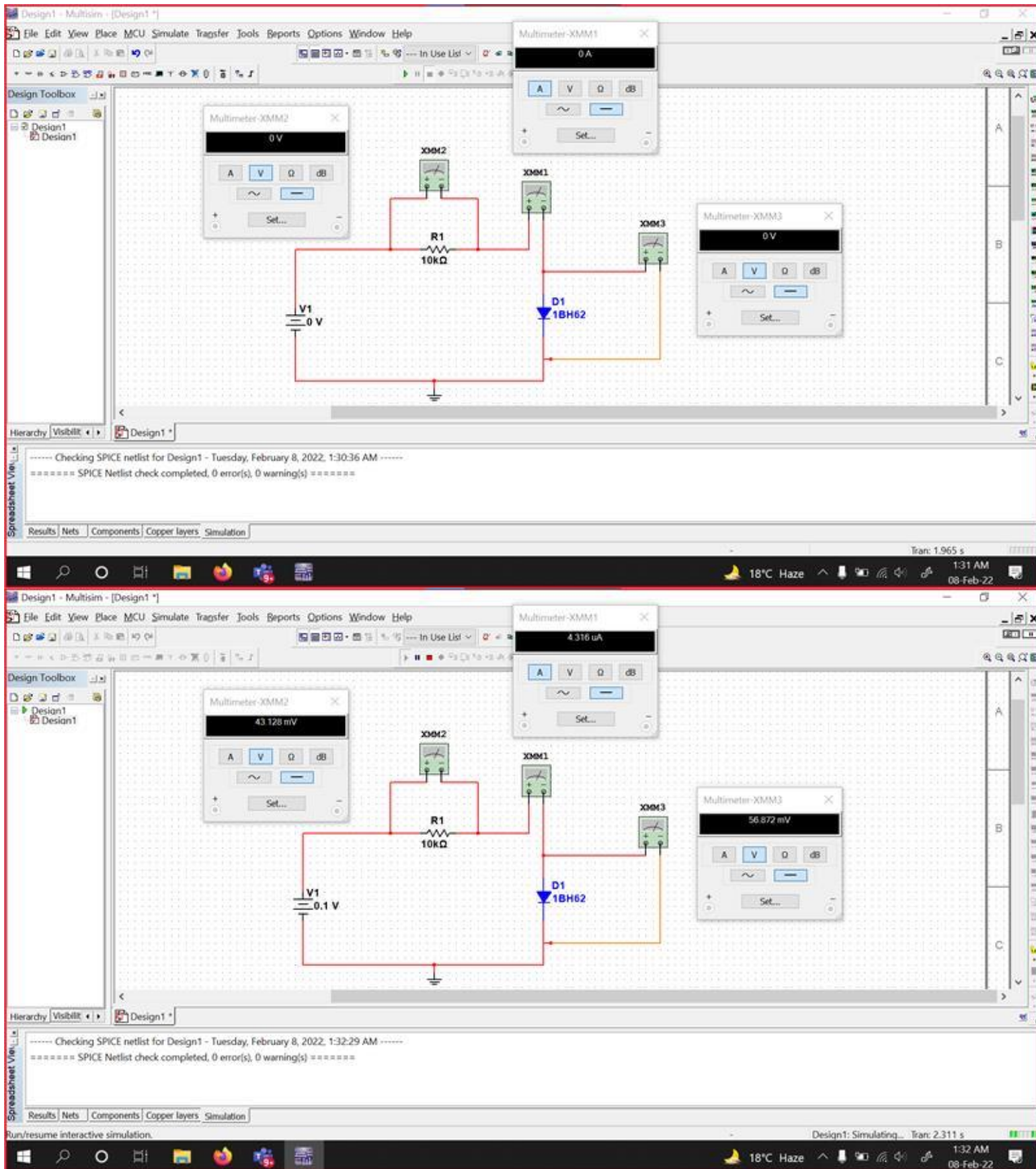


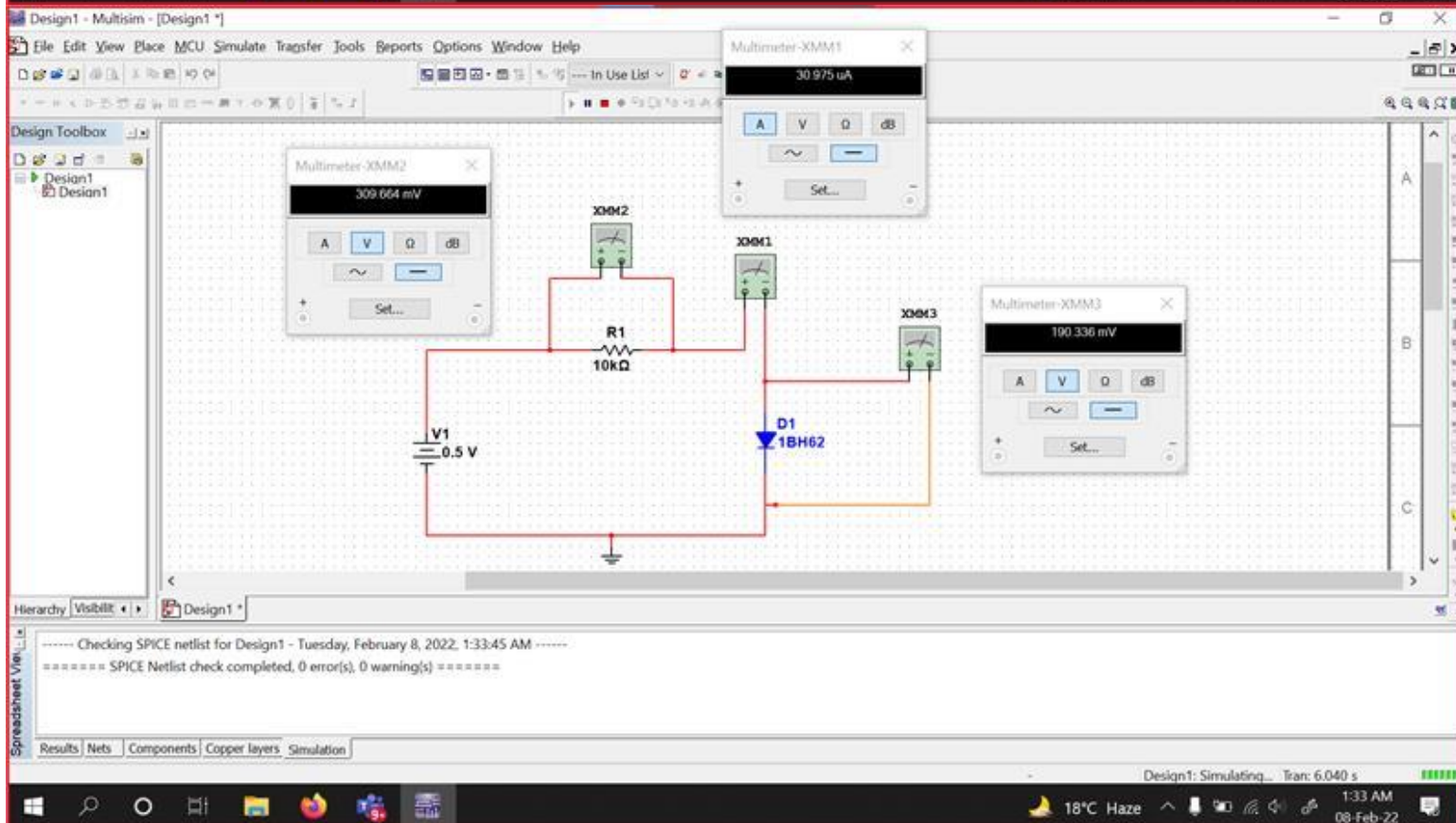
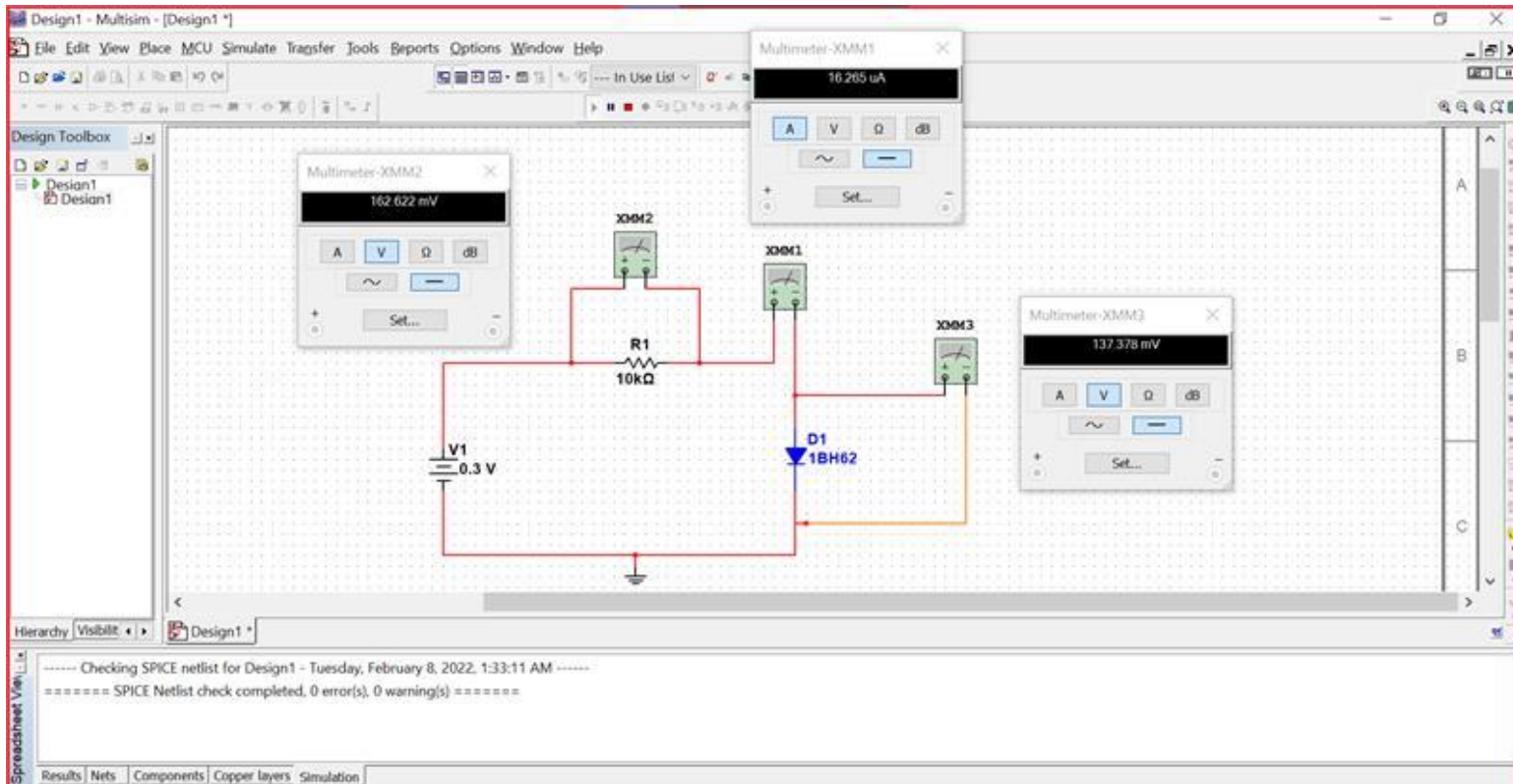
Graph



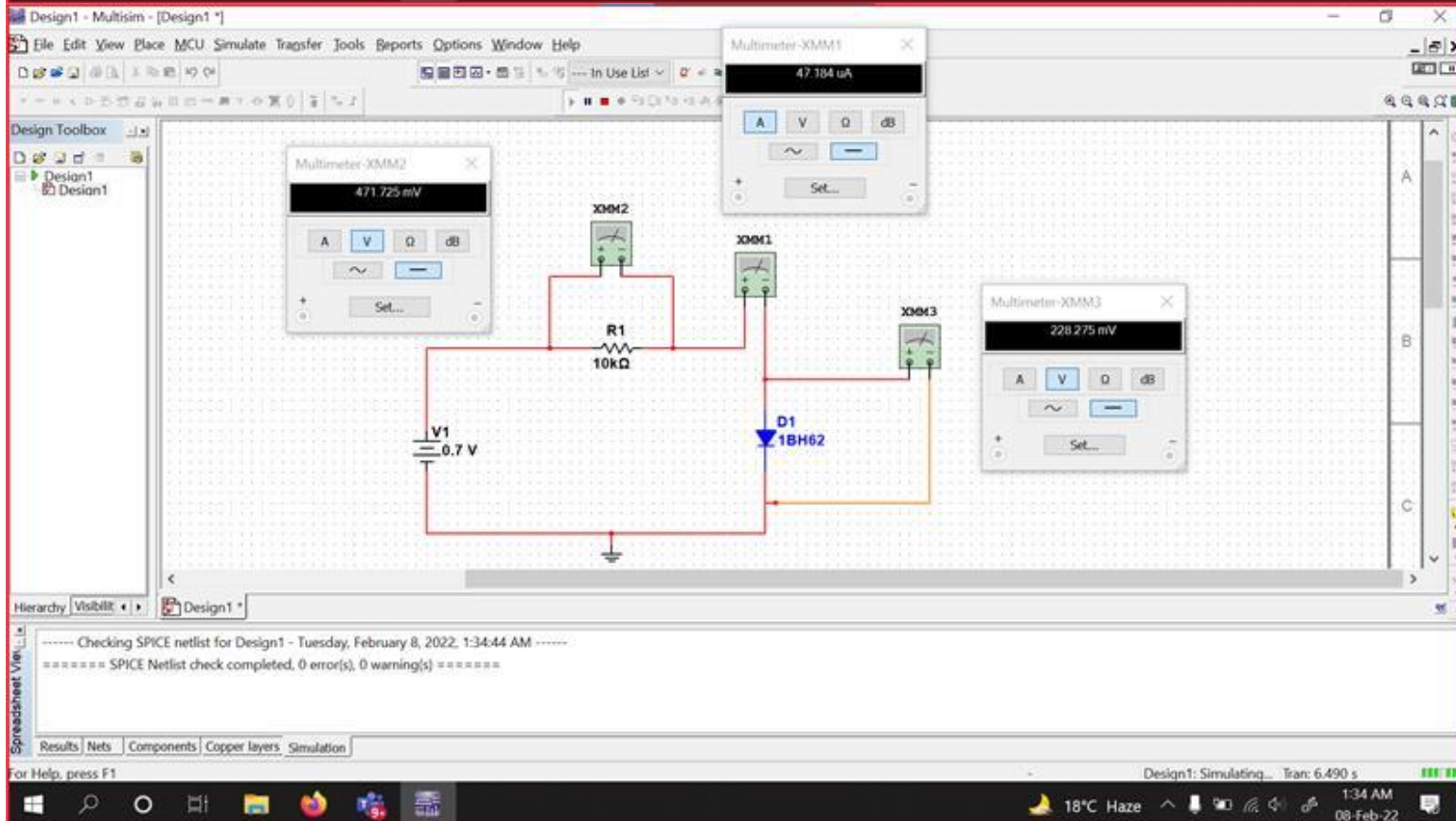
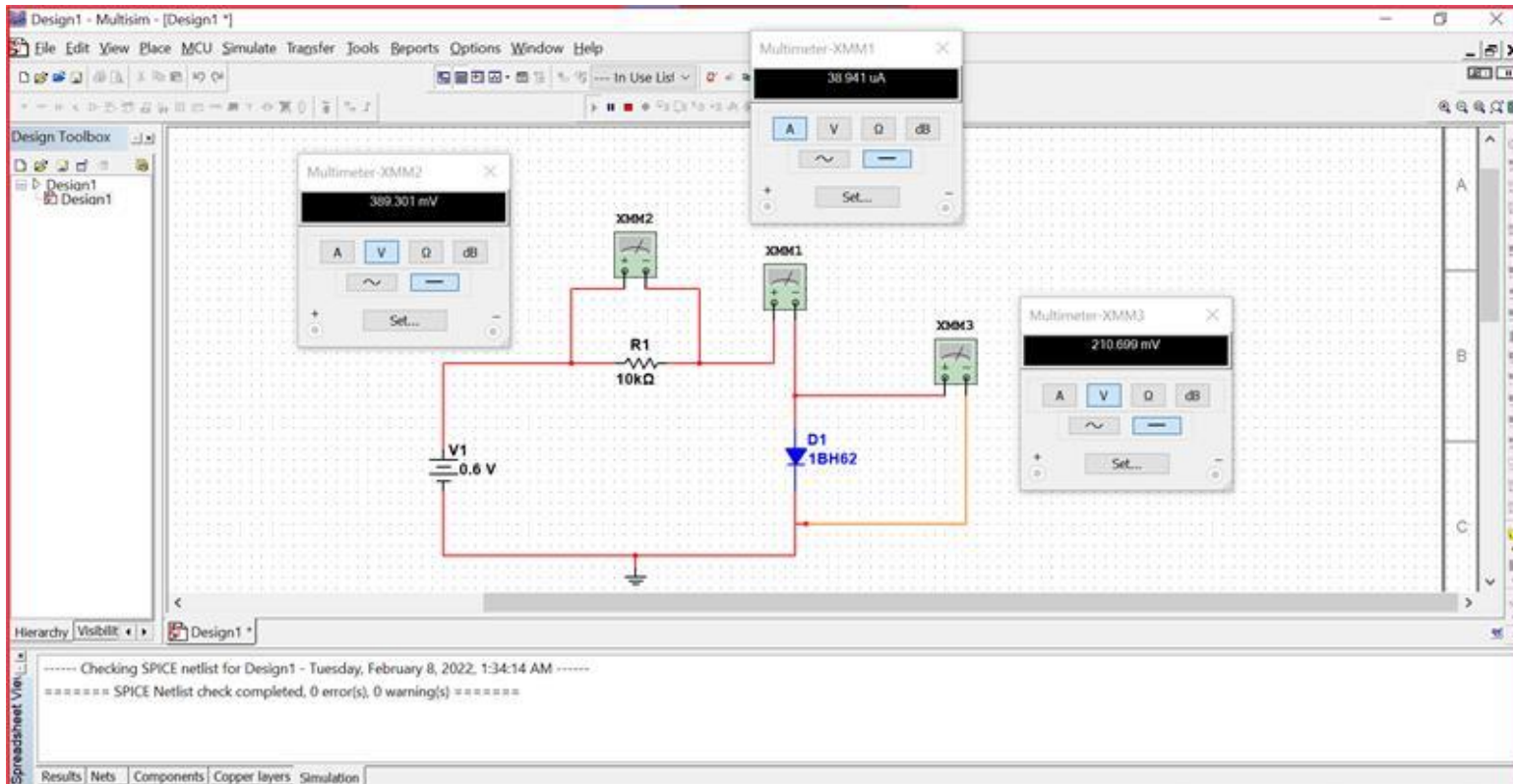


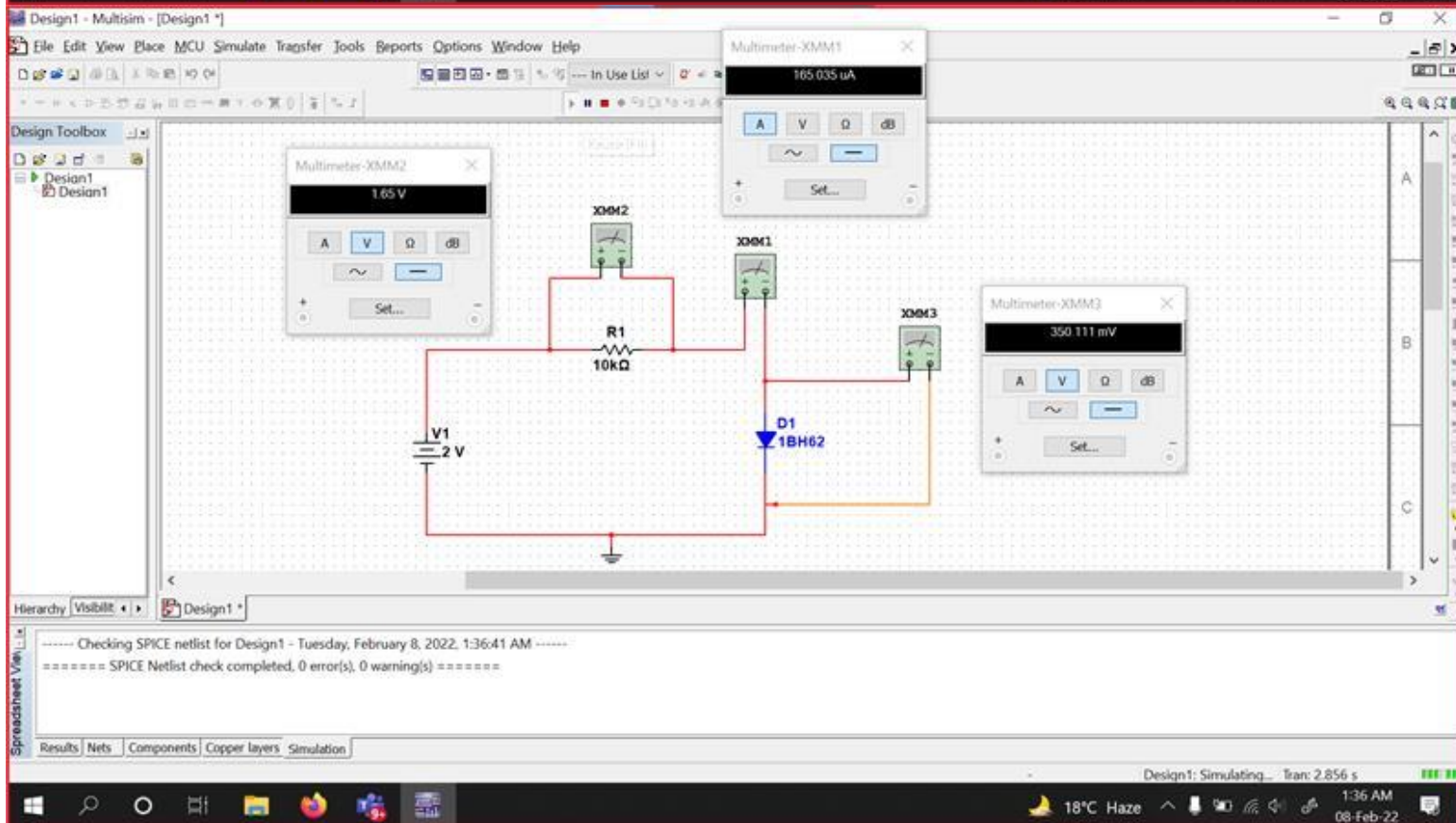
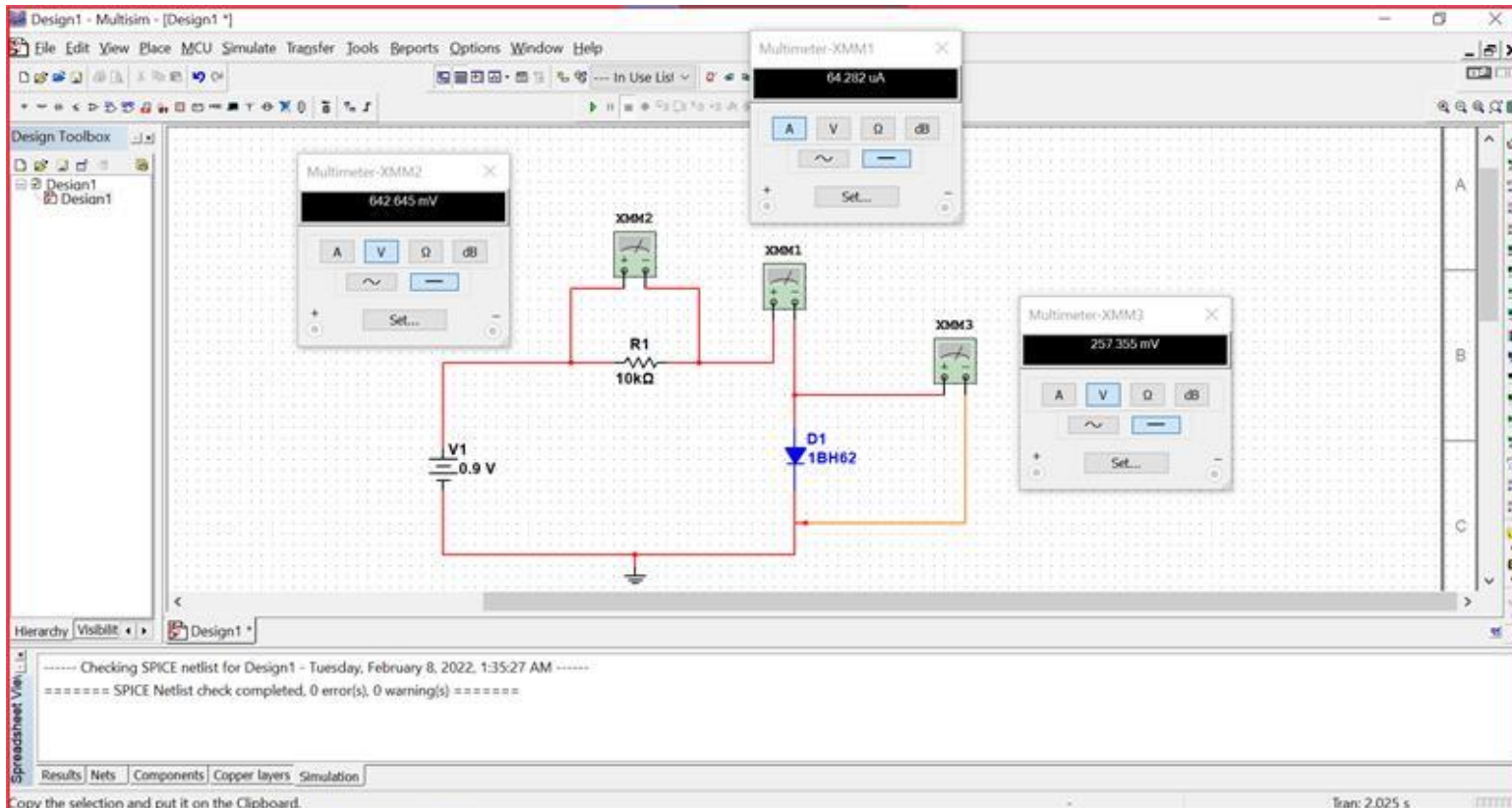
## Simulation:



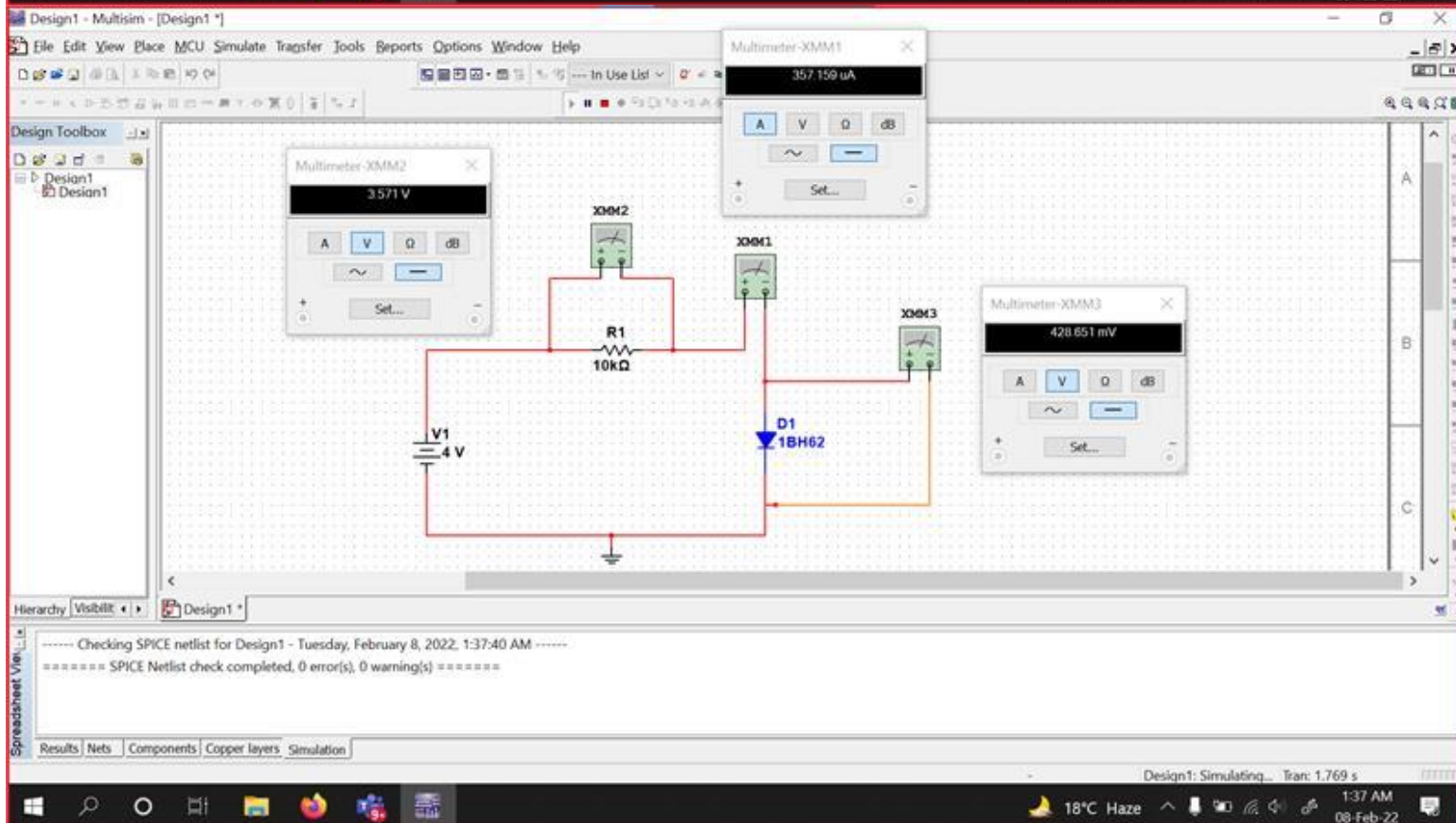
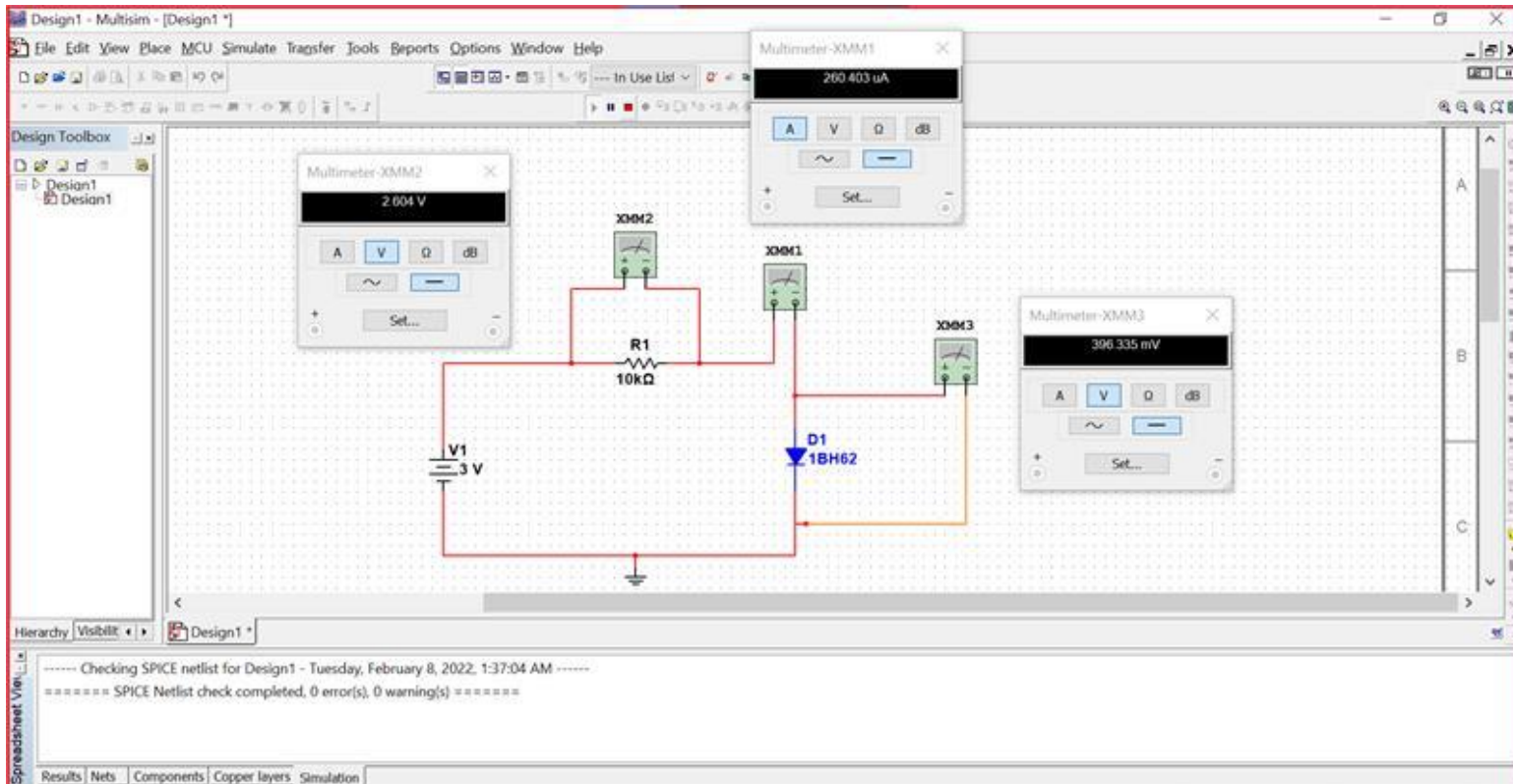


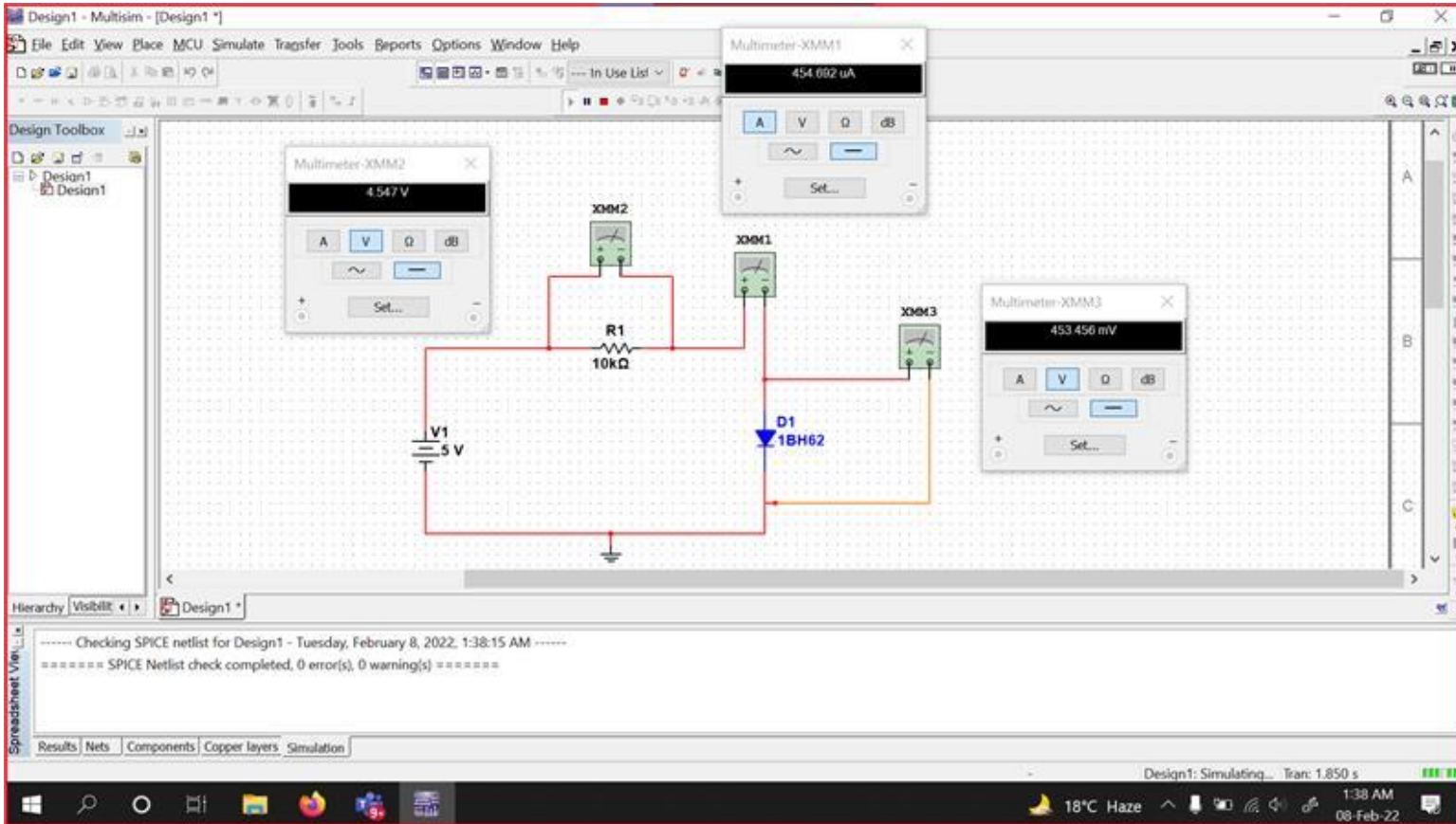














**Here is the drive link of our simulation part,**

<https://drive.google.com/drive/folders/13zr6DkAPRiPGiuaWGRUY42enjekaIYLL?usp=sharing>

### **Discussion:**

From this overall experiment we mainly got to learn about the construction of a semiconductor diode and how to operate a semiconductor diode. Si diode Improved temperature sensitivity and easily available. Electronics have become more sensitive to "Speed" concerns in recent years. The outcome corresponds to the theoretical value. The curves show that the diode's knee of curve is around 0.7 V. It has been proven that our experimental result matches the theoretical outcome using the data table for diode characteristic. As a result, the theory was proven correct, and the experiment went off without a hitch. The entire experiment went off without a hitch.

### **References:**

1. Robert L. Boylestad, Louis Nashelsky, Electronic Devices and Circuit Theory, Ninth Edition, 2007-2008
2. Adel S. Sedra, Kenneth C. Smith, Microelectronic Circuits, Saunders College Publishing, 3rd ed., ISBN: 0-03-051648-X, 1991.
3. American International University–Bangladesh (AIUB) Electronic Devices Lab Manual.
4. David J. Comer, Donald T. Comer, Fundamentals of Electronic Circuit Design, John Wiley & Sons Canada, Ltd.; ISBN: 0471410160, 2002.

**Video Link:** <https://youtu.be/UqJ258EPTkI>





